

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of	)	
	)	
Byeung-leul LEE et al.	)	Group Art Unit: Unassigned
	)	
Application No.: New Application	)	Examiner: Unassigned
	)	
Filed: Herewith	)	
	)	
For: METHOD OF REDUCING	)	
NOTCHING DURING REACTIVE	)	
ION ETCHING	)	

**PRELIMINARY AMENDMENT**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Prior to examination on the merits, kindly amend the above-captioned application as follows:

**IN THE SPECIFICATION:**

Kindly add the following paragraph on page 1, after the title of the invention and before the "Background of the Invention," --Priority is claimed to Patent Application Number 2001-12629, filed in the Republic of Korea on March 12, 2001, herein incorporated by reference.--